## VAKSIS R&D AND ENGINEERING

## PVD handy 2T sm



## **Technical Specifications:**

Base Pressure	$< 5x10^7$ Torr
Leak Rate	< 10 <sup>-8</sup> Torr.l/s
High-speed Pump	300 I/s Diffusion Pump
Mechanical Pump	2.5 m³/h Dual Stage Mechanical Pump
Substrate Size	40 mm diameter
Thickness Measurement	_In-situ measurement with Quartz X-tal Oscillator
Deposition Mode	Upward (all sources)
Number of Sources	2
Max. Current Carrying Capacity	175 Amp.
Control	Full automatic pumping, manual evaporation



2015 Productivity Improvement Project Award by Ministry of Science, Industry and Technology

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